

Name	NSi-01
Structure	$ \begin{array}{c} \text{R4} \quad \text{R1} \\ \quad \\ \text{R5}-\text{Si}-\text{N}-\text{Si}-\text{R2} \\ \quad \\ \text{R6} \quad \text{R3} \\ \quad \quad \text{H} \end{array} $
Boiling point	185°C
Vapor pressure	8.0Torr at 65°C

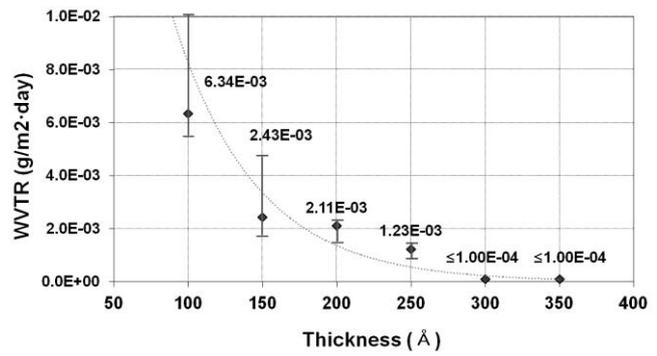


Fig. 1. The physical properties of Si precursor. Fig. 2. WVTR of the deposited SiNx film on PEN film with a various thickness.